

Docket No.: 50432-485



*1765*  
*# 7*  
**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of : Customer Number: 20277  
Wen-Jie QI, et al. : Confirmation Number: 2309  
Serial No.: 10/023,328 : Group Art Unit: 1765  
Filed: December 20, 2001 : Examiner: Lan Vinh  
For: NITRIDE OFFSET SPACER TO MINIMIZE SILICON RECESS BY USING POLY  
REOXIDATION LAYER AS ETCH STOP LAYER

**INFORMATION DISCLOSURE STATEMENT**

Mail Stop No Fee IDS  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RECEIVED**  
**AUG 12 2003**  
**TC 1700**

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached form PTO-1449. It is respectfully requested that the references be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

Each non-English language reference was first cited in a corresponding foreign application search report or office action and its relevance discussed therein. A copy of the

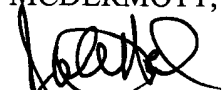
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foreign search report or office action, together with an English language version thereof, is attached for the Examiner's information.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

MCDERMOTT, WILL & EMERY



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**Date: August 11, 2003**

## INFORMATION DISCLOSURE

CITATION IN AN  
APPLICATIONATTY. DOCKET NO.  
**50432-485**SERIAL NO.  
**10/023,328**APPLICANT  
**Wen-Jie Qi, et al.**FILING DATE  
**December 20, 2001**GROUP  
**1765**

(PTO-1449)

## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		US 5,670,404	09/23/1997	Chang-Ming Dai	
		US 5,912,188	06/15/1999	Mark I. Gardner et al.	
		US 6,165,831	12/26/2000	Chen-Chung Hsu	
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## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		EP 0 345 875 A2n	12/13/1999	N. V. Philips			X

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.

EXAMINER

DATE CONSIDERED

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.